

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application. Please cancel claim 6 and amend claims 1, 26, 37 and 45 as follows:

Listing of Claims:

1. (Currently Amended) An apparatus for controlling a temperature of a microelectronic substrate, the substrate having a first surface and a second surface opposite the first surface, the apparatus comprising:

a substrate support having at least one support surface for engaging and supporting the substrate, the support surface being rotatable about an axis extending through the substrate and perpendicular to the first surface and the second surface; and

a temperature controller positioned at least proximate to the substrate support, the temperature controller having a first thermal link coupled with a first portion of the substrate and a second thermal link coupled with a second portion of the substrate, the first and second thermal links being separately controllable for transferring heat to or from the first and second portions at different rates, wherein the first thermal link comprises a first nozzle configured to direct a first fluid stream toward the first portion of the substrate, and the second thermal link comprises a second nozzle configured to direct a second fluid stream toward the second portion of the substrate.

2. (Original) The apparatus of claim 1 wherein the temperature controller is fixed relative to the substrate when the substrate is supported by the substrate support.

3. (Cancelled)

4. (Original) The apparatus of claim 1, further comprising a liquid supply conduit having an opening for dispensing a liquid onto the substrate.

5. (Previously Presented) The apparatus of claim 4 wherein the supply conduit is positioned adjacent the first surface of the substrate when the substrate is supported by the substrate support for disposing the liquid on the first surface, further wherein the first and second thermal links are positioned adjacent the second surface for transferring heat to or from the second surface.

6. (Cancelled)

7. (Original) The apparatus of claim 6, further comprising a source of compressed gas coupled to the first and second nozzles.

8. (Original) The apparatus of claim 7 wherein the source of compressed gas includes a source of compressed air.

9. (Original) The apparatus of claim 6, further comprising a manifold coupled to the first and second nozzles.

10. (Original) The apparatus of claim 6, further comprising a source of liquid coupled to the first and second nozzles.

11-12. (Cancelled)

13. (Original) The apparatus of claim 1 wherein the first thermal link is coupled directly with the first portion of the substrate and the second thermal link is coupled directly with the second portion of the substrate.

14. (Original) The apparatus of claim 1 wherein the first thermal link includes a first electrical element spaced apart from the first portion of the substrate and the second thermal link includes a second electrical element spaced apart from the second portion of the substrate.

15. (Previously Presented) The apparatus of claim 14 wherein the substrate support includes at least one standoff having an engaging surface for engaging the substrate, the engaging surface being spaced apart from the first and second electrical elements.

16. (Original) The apparatus of claim 14 wherein the first electrical element includes a first thermoelectric device and the second electrical element includes a second thermoelectric device, the thermoelectric devices configured to generate a heating effect when current is passed through the devices in a first direction and a cooling effect when current is passed through the devices in an opposite direction.

17. (Original) The apparatus of claim 1 wherein the substrate support is rotatable about a rotation axis and the first thermal link is spaced apart from the rotation axis by a first distance and the second thermal link is spaced apart from the rotation axis by a second distance different than the first distance.

18. (Original) The apparatus of claim 1 wherein the substrate support is rotatable about a rotation axis that extends through the first thermal link.

19. (Original) The apparatus of claim 1 wherein the first and second thermal links are annular relative to an axis extending generally perpendicular to at least one of the first and second surfaces of the substrate.

20. (Original) The apparatus of claim 1 wherein the first and second thermal links are concentric relative to an axis extending generally perpendicular to at least one of the first and second surfaces of the substrate.

21. (Original) The apparatus of claim 1 wherein the first thermal link includes a heat source.

22. (Original) The apparatus of claim 1 wherein the first thermal link includes a cooling source.

23. (Original) The apparatus of claim 1 wherein the substrate support includes rotatable chuck for releasably engaging the substrate.

24. (Original) The apparatus of claim 1 wherein the substrate support includes an upwardly facing bowl for retaining excess fluid that drips from the substrate.

25. (Original) The apparatus of claim 1 wherein the temperature controller includes a temperature sensor for monitoring at least one temperature of the substrate, further wherein the temperature sensor is coupled to the first and second thermal links to maintain the first and second portions of the substrate at approximately the same temperature.

26. (Currently Amended) An apparatus for controlling a temperature of a microelectronic substrate, the substrate having a first surface and a second surface opposite the first surface, the apparatus comprising:

a substrate support having an engaging surface positioned to support a peripheral portion of the second surface of the substrate, the substrate support having an open portion projecting through the substrate support and adjacent the second surface of the substrate to allow direct thermal contact with the second surface, the support being rotatable about an axis extending through the substrate and perpendicular to the first surface and the second surface; and

a temperature controller coupled to a source of gas, the temperature controller having at least one orifice proximate to the substrate support for directing ~~[[an]]~~ a flow of the gas through the ~~open portion~~ at least one orifice that ~~[[and]]~~ directly impinges against the second surface of the substrate.

27. (Original) The apparatus of claim 26 wherein the engaging surface of the substrate support is rotatable relative to the orifice of the temperature controller to rotate the substrate relative to the orifice.

28. (Original) The apparatus of claim 26 wherein the orifice is a first orifice aligned with a first portion of the substrate, the source of gas having a second orifice aligned with a second portion of the substrate, the temperature controller being controllable to transfer heat at a first rate to or from the substrate through the first orifice, the temperature controller being controllable to transfer heat at a second rate to or from the substrate through the second orifice.

29. (Original) The apparatus of claim 26 wherein the source of compressed gas includes a source of compressed air.

30. (Original) The apparatus of claim 26 wherein the source of gas has a temperature less than a temperature of the substrate to cool the substrate.

31. (Original) The apparatus of claim 26 wherein the source of gas has a temperature greater than a temperature of the substrate to heat the substrate.

32. (Original) The apparatus of claim 26, further comprising:
a liquid supply conduit having an opening positioned proximate to the substrate support for disposing a liquid on the substrate; and
a source of the liquid coupled to the liquid supply conduit.

33. (Cancelled)

34. (Previously Presented) The apparatus of claim 26 wherein the substrate support is rotatable about a rotation axis that is approximately perpendicular to the first and second surfaces and the first thermal link is spaced apart from the rotation axis by a first distance and the second thermal link is spaced apart from the rotation axis by a second distance different than the first distance.

35. (Original) The apparatus of claim 26 wherein the substrate support includes a rotatable chuck for releasably engaging the substrate.

36. (Previously Presented) The apparatus of claim 26 wherein the substrate support includes an bowl for retaining excess fluid that drips from the substrate, the bowl facing upwardly towards the second surface.

37. (Currently Amended) An apparatus for controlling a temperature of a microelectronic substrate, the substrate having a first surface and a second surface opposite the first surface, the apparatus comprising:

a substrate support having at least one support surface for engaging and supporting the substrate, the at least one support surface being rotatable about an axis extending through the substrate and perpendicular to the first surface and the second surface; and

a temperature controller positioned at least proximate to the substrate support and being generally fixed relative to the substrate when the substrate is supported by the substrate support, the temperature controller having a first thermal link coupled directly with a first portion of the substrate and a second thermal link coupled directly with a second portion of the substrate, the first and second thermal links being separately controllable for directing a first fluid stream and a second fluid stream transferring heat to or from the respective first and second portions of the substrate to transfer heat to or from the first and second portions of the substrate at different rates.

38. (Original) The apparatus of claim 37 wherein the first thermal link includes a first nozzle having a first orifice directed toward the first portion of the substrate and the second thermal link includes a second nozzle having a second orifice directed toward the second portion of the substrate.

39. (Original) The apparatus of claim 38, further comprising a source of compressed gas coupled to the first and second nozzles.

40. (Original) The apparatus of claim 38, further comprising a source of liquid coupled to the first and second nozzles.

41. (Original) The apparatus of claim 37 wherein the first thermal link includes a first electrical element spaced apart from the first portion of the substrate and the second thermal link includes a second electrical element spaced apart from the second portion of the substrate.

42. (Original) The apparatus of claim 41 wherein the first electrical element includes a first thermoelectric device spaced apart from the first portion of the substrate and the second electrical element includes a second thermoelectric device spaced apart from the second portion of the substrate.

43. (Original) The apparatus of claim 38 wherein the first thermal link includes a heat source.

44. (Original) The apparatus of claim 38 wherein the first thermal link includes a cooling source.

45. (Currently Amended) An apparatus for controlling a temperature of a microelectronic substrate having a first surface and a second surface opposite the first surface, the apparatus comprising:

a first substrate support configured to engage the substrate, the substrate support being rotatable about an axis extending through the substrate and perpendicular to the first surface and the second surface;

a first temperature controller proximate to the first substrate support to transfer heat to or from the substrate while the substrate is engaged by the first substrate support in a generally stationary position relative to the first temperature controller, the first temperature controller having a first thermal link coupled directly with a first portion of the substrate and a second thermal link coupled directly with a second portion of the substrate, the first and second

thermal links being separately controllable for transferring heat to or from the first and second portions at different rates by impinging a first fluid stream and a second fluid stream against respective first and second portions of the substrate;

a second support proximate to the first support and configured to engage the substrate while a liquid material is applied to the substrate, the second support having a rotatable portion for rotating the substrate;

a second temperature controller proximate to the second substrate support to transfer heat to or from the substrate while the liquid material is applied to the substrate and while the substrate rotates, the second temperature controller having a third thermal link directly coupled with the first portion of the substrate and a fourth thermal link directly coupled with the second portion of the substrate, the third and fourth thermal links being separately controllable for transferring heat to or from the first and second portions at different rates by impinging a third fluid stream and a fourth fluid stream against respective third and fourth portions of the substrate; and

a liquid supply conduit having an opening for dispensing the liquid material onto the substrate when the substrate is supported by the second support.

46. (Original) The apparatus of claim 45 wherein at least one of the temperature controllers includes a first nozzle having a first orifice directed to the first portion of the substrate and a second nozzle having a second orifice directed to the second portion of the substrate, the first and second nozzles being coupled to a source of gas for controlling the temperature of the substrate.

47. (Original) The apparatus of claim 45 wherein at least one of the temperature controllers includes a first electrical element spaced apart from the first portion of the substrate and a second electrical element spaced apart from the second portion of the substrate.

48. (Original) The apparatus of claim 47 wherein the first electrical element includes a first thermoelectric device and the second electrical element includes a second thermoelectric device.

49-77. (Cancelled)